

CLAIMS:

1. An optical recording medium comprising a recording layer containing an alloy represented by a general formula: $(\text{Ti}_x\text{M1}_{1-x})_y\text{M2}_{1-y}$, where element M1 is Si or Al, element M2 is an element different from the element M1, x is equal to or larger than 0.3 and equal to or smaller than 0.8, and y is equal to or larger than 0.75 and equal to or smaller than 1.
2. An optical recording medium in accordance with Claim 1, wherein the element M2 is selected from the group consisting of Si, Al and Fe.
3. An optical recording medium in accordance with Claim 1, wherein x is equal to or larger than 0.4 and equal to or smaller than 0.6.
4. An optical recording medium in accordance with Claim 2, wherein x is equal to or larger than 0.4 and equal to or smaller than 0.6.
5. An optical recording medium in accordance with Claim 1, which further comprises a dielectric layer on at least one side of the recording layer.
6. An optical recording medium in accordance with Claim 2, which further comprises a dielectric layer on at least one side of the recording layer.
7. An optical recording medium in accordance with Claim 3, which further comprises a dielectric layer on at least one side of the recording layer.

8. An optical recording medium in accordance with Claim 1, which further comprises dielectric layers on opposite sides of the recording layer.
9. An optical recording medium in accordance with Claim 2, which further comprises dielectric layers on opposite sides of the recording layer.
10. An optical recording medium in accordance with Claim 3, which further comprises dielectric layers on opposite sides of the recording layer.
11. A method for manufacturing an optical recording medium comprising of a step of forming a recording layer of an optical recording medium by a sputtering process using a target that contains an alloy represented by a general formula: $(\text{Ti}_x\text{M1}_{1-x})_y\text{M2}_{1-y}$, where element M1 is Si or Al, element M2 is an element different from the element M1, x' is equal to or larger than 0.37 and equal to or smaller than 0.85 and y' is equal to or larger than 0.75 and equal to or smaller than 1.
12. A method for manufacturing an optical recording medium in accordance with Claim 11, wherein the element M2 is selected from the group consisting of Si, Al and Fe.
13. A method for manufacturing an optical recording medium in accordance with Claim 11, wherein x is equal to or larger than 0.4 and equal to or smaller than 0.6.
14. A method for manufacturing an optical recording medium in accordance with Claim 12, wherein x is equal to or larger than 0.4 and equal to or smaller than 0.6.

15. A target used for a sputtering process that contains an alloy represented by a general formula: $(\text{Ti}_x\text{M1}_{1-x})_y\text{M2}_{1-y}$, where element M1 is Si or Al, element M2 is an element different from the element M1, x' is equal to or larger than 0.37 and equal to or smaller than 0.85 and y' is equal to or larger than 0.75 and equal to or smaller than 1.

16. A target for a sputtering process in accordance with Claim 15, wherein the element M2 is selected from the group consisting of Si, Al and Fe.

17. A target for a sputtering process in accordance with Claim 15, wherein x is equal to or larger than 0.4 and equal to or smaller than 0.6.

18. A target for a sputtering process in accordance with Claim 16, wherein x is equal to or larger than 0.4 and equal to or smaller than 0.6.